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Patent
USSN 09/375,627
Atty Docket 99108

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

HANS LOSCHNER et al.

For: PARTICLE MULTIBEAM LITHOGRAPHY

Serial No. 09/375,627

Filed: August 17, 1999

) Group Art Unit:
1756

) Examiner:
Chris Young

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TECHNOLOGY CENTER 2800

SECOND PRELIMINARY AMENDMENT BEFORE ACTION

TO:

Assistant Commissioner of Patents
Washington, D.C. 20231

Dear Sir:

Applicant requests that the subject application be amended as follows
before action:

IN THE CLAIMS:

Please amend claim 19 as set forth below:

19. (Twice Amended) A method for multibeam lithography by means of electrically charged particles using the apparatus of claim 1, wherein a particle beam is produced by a particle source, transferred into an illuminating beam and formed into a plurality of [sun] sub-beams, the [sun] sub-beams being formed by means of at least one aperture plate having an array of a corresponding plurality of apertures and the [sun] sub-beams are focused onto the surface of a substrate, and wherein the beam position of each [sun] sub-beam is controlled by means of a deflection unit, for correcting individual imaging aberrations of the respective [sun] sub-beam with respect to the desired target position and/or positioning the [sun] sub-beam during a writing process on the substrate surface.

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